

TRADEMARK ASSIGNMENT

Electronic Version v1.1

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SUBMISSION TYPE:	NEW ASSIGNMENT		
NATURE OF CONVEYANCE:	ASSIGNS THE ENTIRE INTEREST AND THE GOODWILL		
CONVEYING PARTY DATA			
Name	Formerly	Execution Date	Entity Type
Vistec IP Holdings Ltd.		07/07/2012	COMPANY: CAYMAN ISLANDS
RECEIVING PARTY DATA			
Name:	Vistec Electron Beam GmbH		
Street Address:	Goeschwitzer Str. 25		
City:	07745 Jena		
State/Country:	GERMANY		
Entity Type:	LIMITED LIABILITY COMPANY: GERMANY		
PROPERTY NUMBERS Total: 3			
Property Type	Number	Word Mark	
Registration Number:	3342560	VISTEC	
Registration Number:	3456195	VISTEC	
Registration Number:	3376869	VISTEC	
CORRESPONDENCE DATA			
Fax Number:	2124464900		
<i>Correspondence will be sent to the e-mail address first; if that is unsuccessful, it will be sent via US Mail.</i>			
Email:	susan.zablocki@kirkland.com		
Correspondent Name:	Susan Zablocki		
Address Line 1:	Kirkland & Ellis LLP		
Address Line 2:	601 Lexington Avenue		
Address Line 4:	New York, NEW YORK 10022		
ATTORNEY DOCKET NUMBER:	42326-1		
DOMESTIC REPRESENTATIVE			
Name:			

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Address Line 1:
Address Line 2:
Address Line 3:
Address Line 4:

NAME OF SUBMITTER:

Susan Zablocki

Signature:

/susan zablocki/

Date:

07/12/2012

Total Attachments: 9

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TRADEMARK ASSIGNMENT

THIS TRADEMARK ASSIGNMENT (this "Assignment") is made and entered into as of this 7 day of July, 2012 ("Effective Date") by and between Vistec IP Holdings Ltd., a Cayman Islands company, with business address at P.O. Box 30967, Uglan House, South Church St., George Town, Grand Cayman, Cayman Islands ("Assignor") and **Vistec Electron Beam GmbH**, a limited liability company (*Gesellschaft mit beschränkter Haftung*), incorporated under the laws of Germany ("Assignee").

WHEREAS, Assignor wishes to assign to Assignee, and Assignee wishes to acquire from Assignor, the entire right, title and interest in and to the trademark registrations and applications set forth on Schedule A attached hereto, and goodwill of the business associated therewith (the "Trademarks").

NOW, THEREFORE, for good and valuable consideration, the receipt and sufficiency of which are hereby acknowledged, Assignor hereby sells, assigns, transfers, and relinquishes to Assignee, its successors, assigns, and legal representatives the entire right, title, and interest in and to the Trademarks for the United States and all foreign countries, whether or not registration is secured, including, without limitation, any applications, renewals or extensions thereof, and in and to all rights corresponding to the foregoing throughout the world, and all the rights embraced therein, in Assignor's possession or under Assignor's control, for Assignee's own use and enjoyment, and for the use and enjoyment of Assignee's successors, assigns or other legal representatives, as fully and entirely as the same would have been held and enjoyed by Assignor if this Assignment had not been made, together with all income, royalties or payments due or payable as of the Effective Date or thereafter, including, without limitation, all claims for damages by reason of past, present or future infringement or other violation, with the right to sue for, and collect the same for Assignee's own use and enjoyment and for the use and enjoyment of its successors, assigns or other legal representatives.

Assignor hereby authorizes and requests the Commissioners of the United States Patent and Trademark Office and the corresponding entity or agency in any applicable foreign country to record Assignee as assignee and new owner of the Trademarks.

At Assignee's reasonable request and expense, Assignor hereby agrees to execute and deliver such further instruments of transfer and assignment and to take such other action as Assignee may reasonably request to more effectively consummate the assignments and assumptions contemplated by this Assignment. Without limiting the foregoing, Assignor will, at Assignee's reasonable request, deliver (unless instructed otherwise by Assignee) to Assignee all relevant forms (as provided by the United States Patent and Trademark Office and the corresponding entity or agency in any applicable foreign country) required to effect the transfer of all Trademarks to Assignee, duly executed on behalf of the Assignor.

* * * * *

State of California

SECRETARY OF STATE

I, DEBRA BOWEN, Secretary of State of the State of California, hereby certify:

That, Uyen Nguyen was, on June 28, 2012, a duly commissioned, qualified and acting NOTARY PUBLIC, in the State of California, empowered to act as such Notary in any part of this State and authorized to take the acknowledgment or proof of powers of attorney, mortgages, deeds, grants, transfers, and other instruments of writing executed by any person, and to take depositions and affidavits and administer oaths and affirmations in all matters incident to the duties of the office or to be used before any court, judge, officer, or board.

I FURTHER CERTIFY that the seal affixed or impressed on the attached document is the official seal of said Notary Public and it appears that the name subscribed thereon is the genuine signature of the person aforesaid, his (or her) signature being of record in this office.

In Witness Whereof, I execute
this certificate and affix the
Great Seal of the State of
California this 3rd
day of July 2012.

Debra Bowen
Secretary of State



IN WITNESS WHEREOF, Assignor has caused this Assignment to be executed by its duly authorized representative as of the Effective Date.

Vistec IP Holdings Ltd.

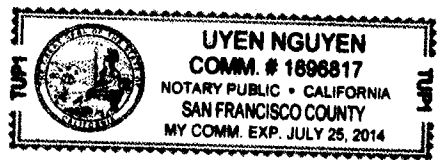
Name: [Signature]
Title: Director

STATE OF California)
) SS:
COUNTY OF San Francisco

Before me this 28 day of JUNE, 2012, personally appeared John Knoll, personally known to me or proved to me on the basis of satisfactory evidence to be the person whose name is subscribed to the within instrument and acknowledged to me that he executed the same in his authorized capacity therefor and that he signed the same of his own free will for the purpose therein expressed.

WITNESS my hand and official seal:

[Signature]
Notary Public



IN WITNESS WHEREOF, Assignee has caused this Assignment to be executed by its duly authorized representative as of the Effective Date.

Vistec Electron Beam GmbH

Name: Wolfgang Dori

Title: Managing Director (*Geschäftsführer*)

STATE OF)
) SS:
COUNTY OF)

Before me this ____ day of _____, 2012, personally appeared _____, personally known to me or proved to me on the basis of satisfactory evidence to be the person whose name is subscribed to the within instrument and acknowledged to me that he executed the same in his authorized capacity therefor and that he signed the same of his own free will for the purpose therein expressed.

WITNESS my hand and official seal:

Notary Public

SCHEDULE A

TRADEMARKS

Trademark	Database	Application Number / Application Date	Registration Number / Registration Date	Status	Goods and Services
VISTEC	U.S. Federal	77001434 9/18/2006	3342560 11/27/2007	Registered	(Int. Cl. 7) machine operated micro lithography equipment; machines for use in the manufacture by micro-lithography, especially of electronic components, namely, integrated circuits, semi-conductors, magnetic domain memories and integral optical systems; parts and fittings for all the aforesaid goods
VISTEC	U.S. Federal	77001479 9/18/2006	3456195 7/1/2008	Registered	(Int. Cl. 9) software for electron beam writing and process technology, in particular, for simulating and optimizing high-resolution electron beam writing and nanometer process technologies; software for the design, testing and fabrication of photographic masks; electronic semi-conductors; integrated circuits; photo-lithographic masks; magnetic heads; chips, namely, chips for testing and investigating genes or other biological molecules, LCD panels, flat panel display screens, magnetic domain memories
VISTEC	U.S. Federal	77001615 9/18/2006	3376869 2/5/2008	Registered	(Int. Cl. 42) research,

Trademark	Database	Application Number / Application Date	Registration Number / Registration Date	Status	Goods and Services
					<p>development and technological consultation in the field of electron beam writing; creation of software for electron beam writing and process technology, in particular for simulating and optimizing high resolution electron beam writing and nanometer process technologies; technological advisory and consultation services in the field of machines, apparatus and instruments for use in the electronics, micro-lithography, semi-conductor, integrated circuit, magnetic domain memories and integrated optical systems industries; design, maintenance and development of computer software for use in the electronics, micro-lithography, semi-conductor, integrated circuit, magnetic domain memories and integrated optical systems industries and for the design, testing and fabrication of photo-lithographic masks; technological advisory and consultation services in connection with the design, testing and fabrication of photo-lithographic masks</p>
VISTEC	Germany	30671107.9 11/20/2006	30671107 3/21/2007	Registered	

Trademark	Database	Application Number / Application Date	Registration Number / Registration Date	Status	Goods and Services
VISTEC	China	5665791 10/17/2006	5665791 3/28/2010	Registered	
VISTEC	China	5665793 10/17/2006	5665793 7/7/2010	Registered	
VISTEC	China	5665792 10/17/2006	5665792 7/7/2010	Registered	
vistec	Singapore	T0619195C 9/14/2006		Registered	07 Patterning mechanisms [machines] for patterning of structures based on electron beam technology, other than for office use; machines for use in the manufacture by micro-lithography; parts and fittings for all the aforesaid goods.
vistec	Singapore	T0619196A 9/14/2006		Registered	09 Software for electron beam writing and process technology, in particular for simulating and optimizing high-resolution electron beam writing and nanometer process technologies; apparatus and instruments for use in the electronics, (micro)lithography, semi-conductors, integrated circuits, magnetic domain memories and integrated optical systems industries; parts and fittings for all the aforesaid goods; software for use in the electronics, (micro) lithography, semi-conductor, integrated circuit, magnetic domain memory and integrated optical

Trademark	Database	Application Number / Application Date	Registration Number / Registration Date	Status	Goods and Services
					systems industries; software for the design, testing and fabrication of photographic masks; semi-conductors; integrated circuits; photo-lithographic masks [scientific]; magnetic heads, chips [integrated circuits], gene chips, LCDs, display screens, magnetic domain memories, integrated optical systems.
vistec	Singapore	T0619197Z 9/14/2006		Registered	42 Research, development and technological consultancy in the field of electron beam writing; creation of software for electron beam writing and process technology, in particular for simulating and optimizing high resolution electron beam writing and nanometer process technologies; technological advisory and consultancy services in connection with machines, apparatus and instruments for use in the electronics, (micro)lithography, semi-conductor, integrated circuit, magnetic domain memories and integrated optical systems industries; design, maintenance and development of computer software for use in the electronics, (micro)lithography, semi-conductor,

Trademark	Database	Application Number / Application Date	Registration Number / Registration Date	Status	Goods and Services
					integrated circuit, magnetic domain memories and integrated optical systems industries and for the design, testing and fabrication of photo-lithographic masks; technological advisory and consultancy services in connection with the design, testing and fabrication of photo-lithographic masks.
VISTEC	South Korea	45-2006-0003425 9/18/2006	4500241140000 8/4/2008	Registered	
VISTEC	Taiwan	095050789 10/5/2006	01302091 2/16/2008	Registration	